

WHAT IS CLAIMED IS:

- 1                   1.       A method of controlling movement of one or more stages of a  
2 precision assembly to process a substrate having a plurality of process regions, the method  
3 comprising:  
4                   dividing the substrate into blocks according to one or more preset criteria,  
5 each block of the substrate including one or more process regions;  
6                   generating learning data for one or more representative process regions for  
7 each block of the substrate; and  
8                   using the generated learning data of the one or more representative process  
9 regions of each block to control movement of the one or more stages to process the block of  
10 one or more process regions of the substrate.
- 1                   2.       The method of claim 1 wherein the blocks comprise at least one center  
2 block in a center region of the substrate and at least one edge block in an edge region of the  
3 substrate.
- 1                   3.       The method of claim 2 wherein each center block is larger in area than  
2 each edge block.
- 1                   4.       The method of claim 1 wherein the blocks comprise a block having a  
2 row of process regions along a stepping direction and transverse to a scanning direction for a  
3 step-and-scan processing of the substrate.
- 1                   5.       The method of claim 1 wherein the blocks comprise a block having a  
2 plurality of process regions selected from a row of process regions along a stepping direction  
3 and transverse to a scanning direction for a step-and-scan processing of the substrate.
- 1                   6.       The method of claim 1 wherein dividing the substrate into blocks  
2 comprises selecting process regions having substantially the same force effects and grouping  
3 the selected process regions into a block.
- 1                   7.       The method of claim 1 wherein dividing the substrate into blocks  
2 comprises selecting process regions having substantially the same stage position errors and  
3 grouping the selected process regions into a block.

1                   8.       The method of claim 1 wherein dividing the substrate into blocks  
2 comprises selecting process regions having substantially the same center of gravity  
3 calibration errors and grouping the selected process regions into a block.

1                   9.       The method of claim 1 wherein the blocks comprise a block having  
2 process regions which are spaced from each other by other process regions.

1                   10.      The method of claim 1 wherein generating learning data comprises  
2 performing an iterative learning control process on iterative learning control input data which  
3 is selected from the group consisting of a following error of the one or more stages and a  
4 force command of the one or more stages.

1                   11.      The method of claim 1 wherein generating learning data comprises  
2 generating a force feedforward to be applied to the one or more stages.

1                   12.      The method of claim 11 wherein generating learning data comprises  
2 performing a control process on learning control input data which is selected from the group  
3 consisting of a following error of the one or more stages and a force command of the one or  
4 more stages.

1                   13.      The method of claim 1 wherein generating learning data comprises  
2 generating a position feedforward control to fine-adjust a following error of the one or more  
3 stages which is processed by a feedback control to control movement of the one or more  
4 stages.

1                   14.      The method of claim 13 wherein generating learning data comprises  
2 performing a control process on learning control input data which comprises a following  
3 error of the one or more stages.

1                   15.      The method of claim 1 further comprising performing at least one of  
2 interpolating or extrapolating the learning data generated for the representative process  
3 regions to generate additional learning data for other process regions; and using the additional  
4 learning data to control movement of the one or more stages to process the other process  
5 regions of the substrate.

1                   16.     A system of controlling movement of one or more stages of a precision  
2 assembly to process a substrate having a plurality of process regions, the system comprising:  
3                   a position compensation module configured to generate learning data for one  
4 or more representative process regions for each block of a plurality of blocks of a substrate,  
5 each block including one or more process regions; and  
6                   a stage control module configured to use the generated learning data of the one  
7 or more representative process regions of each block to control movement of the one or more  
8 stages to process the block of one or more process regions of the substrate.

1                   17.     The system of claim 16 wherein the position compensation module is  
2 configured to perform an iterative learning control process on iterative learning control input  
3 data which is selected from the group consisting of a following error of the one or more  
4 stages and a force command of the one or more stages.

1                   18.     The system of claim 16 wherein the position compensation module is  
2 configured to generate a force feedforward to be applied to the one or more stages.

1                   19.     The system of claim 16 wherein the position compensation module is  
2 configured to generate a position feedforward control to fine-adjust a following error of the  
3 one or more stages which is processed by a feedback control to control movement of the one  
4 or more stages.

1                   20.     The system of claim 16 wherein the position compensation module is  
2 configured to perform at least one of interpolating or extrapolating the learning data  
3 generated for the representative process regions to generate additional learning data for other  
4 process regions; and use the additional learning data to control movement of the one or more  
5 stages to process the other process regions of the substrate.

1                   21.     A system for controlling movement of one or more stages of a  
2 precision assembly to process a substrate having a plurality of process regions, the system  
3 having one or more memories, the one or more memories comprising:  
4                   code for generating learning data for one or more representative process  
5 regions for each block of a plurality of blocks of a substrate, each block including one or  
6 more process regions; and

7 code for using the generated learning data of the one or more representative  
8 process regions of each block to control movement of the one or more stages to process the  
9 block of one or more process regions of the substrate.

1 22. The system of claim 21 wherein the code for generating learning data  
2 comprises code for performing an iterative learning control process on iterative learning  
3 control input data which is selected from the group consisting of a following error of the one  
4 or more stages and a force command of the one or more stages.

1 23. The system of claim 21 wherein the code for generating learning data  
2 comprises code for generating a force feedforward to be applied to the one or more stages.

1 24. The system of claim 21 wherein the code for generating learning data  
2 comprises code for generating a position feedforward control to fine-adjust a following error  
3 of the one or more stages which is processed by a feedback control to control movement of  
4 the one or more stages.

1 25. The system of claim 21 wherein the code for generating learning data  
2 comprises code for performing at least one of interpolating or extrapolating the learning data  
3 generated for the representative process regions to generate additional learning data for other  
4 process regions; and using the additional learning data to control movement of the one or  
5 more stages to process the other process regions of the substrate.

1 26. A method of operating an exposure apparatus comprising:  
2 reciting a substrate with a stage;  
3 controlling movement of the stage utilizing the method of claim 1; and  
4 exposing the substrate with radiant energy.

1 27. A method for making a micro-device including at least the  
2 photolithography process, wherein the photolithography process utilizes the method of  
3 operating an exposure apparatus of claim 26.

1 28. A method for making a wafer utilizing the method of operating an  
2 exposure apparatus of claim 26.

1 29. A stage device comprising:  
2 a stage that retains an object; and

3                   the system of claim 16;  
4                   wherein the system is configured to control the movement of the stage that  
5 retains the object.

1                   30.     An exposure apparatus comprising:  
2                   an illumination system that irradiates radiant energy; and  
3                   the stage device according to claim 29, the stage device carrying the object  
4 disposed on a path of the radiant energy.